

**PATENT****IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Application of:

**CHRISTIAN ZISTL, ET AL**

Serial No.: 09/634,209

Filed: AUGUST 9, 2000

**For: IMPROVED DEPTH OF FOCUS (DOF)  
FOR TRENCH-FIRST-VIA-LAST (TFVL)  
DAMASCENE PROCESSING WITH  
HARD MASK AND LOW VISCOSITY  
PHOTORESIST**

Group Art Unit: 2814

Examiner: H. Pham

Atty. Dkt. No.: 2000.046600

**DECLARATION UNDER 37 C.F.R. § 1.131 OF MARK W. SINCELL**

1. My name is Mark W. Sincell. I am a patent agent in the firm of Williams, Morgan & Amerson. I have personal knowledge of the facts stated herein.

2. On January 14, 2000, a request was received from AMD's legal department to prepare a United States patent application for the invention described in invention disclosure form number TT3851. See Exhibit A. The invention disclosure form is signed by Christian Zistl, Ting Tsui, and Steven K. Park, and it is dated October 20, 1999.

3. At some point after January 14, 2000, the invention disclosure form number TT3851 was reviewed and an initial draft of a patent application for the invention described in the invention disclosure form was prepared.

4. On March 23, 2000, the initial draft of the application was sent to the inventors. See Exhibit B.

5. At some time after March 23, 2000, comments from the inventors regarding the initial draft application were received. To the extent necessary, the application was revised.

6. On May 24, 2000, a revised copy of the application was sent along with formal papers (assignment, declaration and power of attorney) to AMD for review and the possible execution of the formal papers by the inventors. See Exhibit C.

7. The formal papers for the application were signed on June 13, 2000 by inventor Park, on June 19, 2000 by inventor Zistl, and on July 3, 2000 by inventor Tsui.

8. I understand that willful false statements and the like so made are punishable by fine or imprisonment, or both, and may jeopardize the validity of the application or any patent issuing thereon.

9. I declare under penalty of perjury that the foregoing is true and correct.

Date: 11/03/04

  
Mark W. Sincell